

CLAIMS:

1. A polishing pad used for manufacturing a glass substrate of an information recording medium by polishing a surface of a glass workpiece, the polishing pad comprising:
5 a nap layer having an inner layer and an outer layer, wherein the inner layer that contains a plurality of closed cells, and a plurality of pores are formed on the surface of the outer layer, and wherein the sizes of pores are minute
10 compared to those of the closed cells.
2. The polishing pad according to claim 1, wherein the number of the pores is 400 to 10,000 in 1 mm².
- 15 3. The polishing pad according to claim 1, wherein the compression deformation amount is 40 to 60 μm.
4. The polishing pad according to claim 1, wherein the opening sizes of the pores are 10 to 60 μm.
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5. The polishing pad according to claim 1, wherein the polishing pad is made of polyurethane.
6. The polishing pad according to claim 1, wherein the
25 nap layer is formed on a surface of a base material.
7. The polishing pad according to claim 6, wherein the base material is made of unwoven fabric.
- 30 8. A method for manufacturing a glass substrate of an information recording medium by polishing a surface of a glass workpiece with a polishing pad,
wherein polishing includes a first polishing step for subjecting a surface of the glass workpiece to rough polishing,
35 and a second polishing step for subjecting the surface of the

glass workpiece to precision polishing so that the surface is further smoothed,

wherein the polishing pad is used in the second polishing step.

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9. The method according to claim 8, wherein the number of pores on the polishing pad is 400 to 10,000 in 1 mm².

10. The method according to claim 8, wherein the compression deformation amount of the polishing pad is 40 to 60 μm.

11. The method according to claim 8, wherein the opening sizes of the pores are 10 to 60 μm

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12. The method according to claim 8, wherein the glass workpiece is one of a plurality of glass workpieces that are simultaneously polished, wherein the variation of the thickness of removal layers of the glass workpieces is equal to or less than 0.2 μm.

13. A glass substrate of an information recording medium, manufactured by the method according to claim 8,

wherein, when measured with a three-dimensional external structure analysis microscope at a wavelength (λ) of 0.2 to 1.4 μm, the height (NRa) of micro-waviness on the surface is equal to or less than 0.15 nm.

14. A method for manufacturing a polishing pad, wherein the polishing pad is formed by sliding a pad dresser made of a metal disk, on surface of which diamond abrasive grains are electrodeposited, against a non-buff pad made of foam to polish the non-buff pad.

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